## Yi-Ting Wu

## List of Publications by Year in descending order

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2258059 1872680 7 41 3 6 citations h-index g-index papers 7 7 7 57 docs citations citing authors times ranked all docs

| # | Article   | IF  | CITATIONS |
|---|---|-----|-----------|
| 1 | Simulation-Based Study of Hybrid Fin/Planar LDMOS Design for FinFET-Based System-on-Chip<br>Technology. IEEE Transactions on Electron Devices, 2017, 64, 4193-4199.                             | 3.0 | 25        |
| 2 | Simulation-Based Study of Si/Si <sub>0.9</sub> Ge <sub>0.1</sub> /Si Hetero-Channel FinFET for Enhanced Performance in Low-Power Applications. IEEE Electron Device Letters, 2019, 40, 363-366. | 3.9 | 4         |
| 3 | Cell Ratio Tuning for High-Density SRAM Voltage Scaling With Inserted-Oxide FinFETs. IEEE Electron Device Letters, 2016, 37, 1539-1542.   | 3.9 | 3         |
| 4 | Simulation-Based Study of High-Density SRAM Voltage Scaling Enabled by Inserted-Oxide FinFET Technology. IEEE Transactions on Electron Devices, 2019, 66, 1754-1759.                            | 3.0 | 3         |
| 5 | Simulation-Based Study of Low Minimum Operating Voltage SRAM With Inserted-Oxide FinFETs and Gate-All-Around Transistors. IEEE Transactions on Electron Devices, 2022, 69, 1823-1829.           | 3.0 | 3         |
| 6 | Simulation-Based Study of High-Permittivity Inserted-Oxide FinFET With Low-Permittivity Inner Spacers. IEEE Transactions on Electron Devices, 2021, 68, 5529-5534.                              | 3.0 | 2         |
| 7 | High-density SRAM voltage scaling enabled by inserted-oxide FinFET technology. , 2017, , .  |     | 1         |